ICN2
Nanofabrication Facility

Internal User Registration Form

DATE: / /

INTERNAL USER Nº:

User Name and Surname:	
Group:	
Group Leader:	
Job Position:	
Office nº:	
Phone Number:	
E-mail:	

RESEARCH INFO

RESEARCH ACTIVITY FIELD:

SPECIFIC LABWARE:

Group Leader Signature:

User Signature:

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Select the equipment intended to be used:

Direct Write Laser Lithography	
Mask Aligner UV Photolithography	
Nanoimprint Lithography (NIL)	
E-beam thin film evaporator	
ICP- Reactive Ion Etching (ICP-RIE)	
Sputter Coater (Au)	
Plasma Cleaner (O_2)	
Wet bench	
Oven/Hot plates	
Spinner	
Stylus Profilometer	
3D Optical Profiler	
Optical Microscope	
AFM	
EBL	
FIB	

TERMS AND CONDITIONS:
Signing this document implies that:

1.- The user has read the documentation related to the rules and conditions of use of the Nanofabrication Facility. http://www.icn2.cat/nanofabrication/nanofab.html

2. - The user must cite the Nanofabrication Facility in publications arising from the service provided.

3. - ICN2 is not responsible for property and/or personal damage arising from misuse of facilities and/or violation of safety rules and emergency plan of the building.

4. - Violation of these rules will result in the loss of rights of use of the equipment and services of the Nanofabrication Facility.